

IN THE ABSTRACT

Please cancel the current abstract and insert the following. A marked-up copy showing the changes made to the abstract is attached hereto in Appendix A.

1
-- An exposure apparatus includes an illuminating optics unit for irradiating a reticle, on which a predetermined pattern has been formed, with exposing light emitted from an exposing light source, a reticle stage on which the reticle is placed, a projection optics unit for projecting the predetermined pattern of the reticle onto a substrate, and a substrate stage on which the substrate is placed. The exposure apparatus also includes at least one chamber for internally accommodating the illuminating optics unit, the reticle stage, the projection optics unit and the substrate stage, a first pressure control device for making pressure inside the projection optics unit higher than pressure outside the chamber, and a first correction device for correcting optical characteristics of the projection optics unit in accordance with a value of pressure inside the projection optics unit. --

IN THE SPECIFICATION:

Please amend the specification as follows:

Please substitute the paragraph beginning at page 1, line 8, with the following. A marked-up copy of this paragraph, showing the changes made thereto, is attached in Appendix A.

2
-- This invention relates to an exposure apparatus in which the exposing light used is short-wavelength ultraviolet light, especially, light emitted by a light source such as an excimer laser, a harmonic laser or a mercury lamp and having an emission spectral line that overlaps the